

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re United States Patent Application of:)	Docket No.:	020732-97.668 (7493)
Applicants:	RATH, Melissa K., et al.)	Conf. No.:	4823
Application No.:	10/792,038)	Art Unit:	1752
Date Filed:	March 3, 2004)	Examiner:	LE, Hoa Van
Title:	COMPOSITION AND PROCESS FOR POST-ETCH REMOVAL OF PHOTORESIST AND/OR SACRIFICIAL ANTI-REFLECTIVE MATERIAL DEPOSITED ON A SUBSTRATE)))))	Customer No.:	24239

AMENDMENT RESPONDING TO MAY 6, 2008 OFFICE ACTION AND REQUEST FOR A
ONE-MONTH EXTENSION UNDER 37 CFR §1.136(a) IN UNITED STATES PATENT
APPLICATION NO. 10/792,038

Mail Stop AF
Commissioner for Patents
PO Box 1450
Alexandria, VA 22313-1450

Sir:

This responds to the May 6, 2008 Office Action in the above-identified application.

Please amend the claims, as set out in the following **Section I (the Claims)**.

Remarks addressing the substance of the May 6, 2008 Office Action are set out in the **Section II (Remarks)** hereof.